

ABSTRACT OF THE DISCLOSURE
PATTERN FORMING APPARATUS, DECIDING METHOD, PROGRAM,
INFORMATION PROCESSING APPARATUS, AND ARTICLE
MANUFACTURING METHOD

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The present invention provides a pattern forming apparatus including a detection optical system configured to obtain optical information of a mark provided on a substrate by detecting the mark, and a processing unit configured to perform a process of obtaining a position of the mark by using a template for
10 obtaining the position of the mark by being applied to the optical information of the mark and a window which indicates a region for extracting an amount of characteristic indicating the position of the mark from a waveform signal obtained from the optical information, wherein the processing unit decides, based on the optical information of the mark obtained by the detection optical system, a
15 parameter indicating at least one of a shape of the template and a shape of the window for each of a plurality of substrates.

(Figure 9)